

Notic of Referenc s Cited

Application/Control No.

09/761,753

Applicant(s)/Patent Under
Reexamination
ISHIDA ET AL.

Examiner

Fernando Toledo

Art Unit

2823

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	C	US-5915172-A	06-1999	Noumi et al.	438/151
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	U	✓ Wolf and Tauber; Silicon Processing for the VLSI Era Volume 1: Process Technology, pp. 332, 452 - 453; Lattice Press 1986; Sunset Beach, California
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.